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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: Gil et al. **GROUP:** 1756

SERIAL NO: 10/677,173 **EXAMINER:** Chacko Davis, Daborah

FILED: October 2, 2003

FOR: SYSTEM AND METHOD FOR FABRICATION AND REPLICATION OF DIFFRACTIVE OPTICAL ELEMENTS FOR MASKLESS LITHOGRAPHY

Commissioner of Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INFORMATION DISCLOSURE STATEMENT

In compliance with 37 C.F.R. §§1.56, 1.97, and 1.98, Applicant submits copies of the documents listed on the attached Form PTO-1449. Also enclosed is a check for $180.00.

The Commissioner is authorized to charge Deposit Order Account No. 19-0079 for any further fee that is required in connection with the above referenced application.

Respectfully submitted,

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CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.10

I hereby certify that this Information Disclosure Statement and the documents referred to as enclosed therein are being deposited with the United States Postal Service addressed to the: Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313-1450

Meghan H. Carr

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Form PTO-1449	Gauthier & Connors, LLP 225 Franklin Street Boston, MA 02110 Telephone: (617)426-9180	ATTORNEY DOCKET NO. **MIT.9996**	SERIAL NO. **10/677,173**
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT **Gil et al.** FILING DATE **October 2, 2003**	GROUP **1756** EXAMINER **Chacko David, Daborah**

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-class	Filing Date if Appropriate
	AA						
	AB						

FOREIGN PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation Yes No
	AC						
	AD						

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, etc.)

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EXAMINER	**DATE CONSIDERED**
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	